



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Douglas D. Coolbaugh, et al. **Examiner:** Unassigned

Serial No: 10/605,439

Art Unit: Unassigned

Filed: 9/30/03

Docket: BUR920020094US1 (16895)

For: PRECISION POLYSILICON
RESISTOR PROCESS

Dated: 11/13/03

Commissioner for Patents
United States Patent Office
Alexandria, VA 22313-1450

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Sir:

In accordance with 37 C.F.R. §§ 1.97 and 1.98, it is requested that the following references, which are also listed on the attached Form PTO-1449, be made of record in the above-identified case.

1. Japanese Patent Publication No. JP5275619, dated October 22, 1993;
2. C.H. Lee, IBM Disclosure Bulletin "Polysilicon Resistors Compatible with Bipolar Integrated Circuits and Method of Manufacture", Vol. 25, No. 5, October 1982;
and
3. G.R. Goth, et al., IBM Disclosure Bulletin "Planar Self-Aligned Metal/Sidewall and Polysilicon-Resistor Process", Vol. 25, No. 2, July 1982.

CERTIFICATE OF MAILING UNDER 37 C.F.R. §1.8(a)

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, Box 1450, Alexandria, VA 22313-1450 on

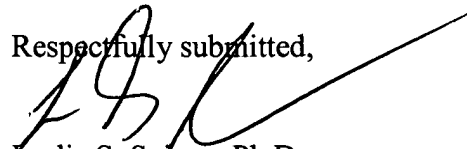
Dated: 11/13/03

Maryann Lusi
Maryann Lusi

Applicants are submitting copies of the above-cited references.

Inasmuch as this Information Disclosure Statement is being submitted in accordance with the schedule set out in 37 C.F.R. § 1.97(b), no statement or fee is required.

Respectfully submitted,



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Enclosure PTO 1449
Three (3) references

Atty. Docket N .
BUR920020094US1 (16895)

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Applicant
Douglas D. Coolbaugh, et al.

Filing Date

Group
Unassigned

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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| | | C.H. Lee, IBM Disclosure Bulletin "Polysilicon Resistors Compatible with Bipolar Integrated Circuits and Method of Manufacture", Vol. 25, No. 5, October 1982; and |
| | | G.R. Goth, et al., IBM Disclosure Bulletin "Planar Self-Aligned Metal/Sidewall and Polysilicon-Resistor Process", Vol. 25, No. 2, July 1982. |
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EXAMINER

DATE CONSIDERED

* EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.